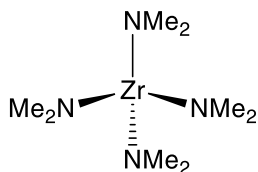


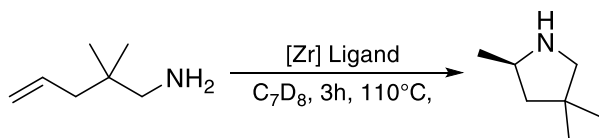
Catalog # 40-4115 Tetrakis(dimethylamino)zirconium(IV), 98% (99.99%-Zr) PURATREM TDMAZ



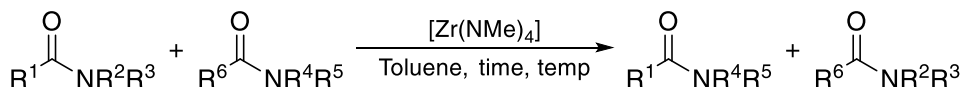
Catalysis Applications

Technical Notes:

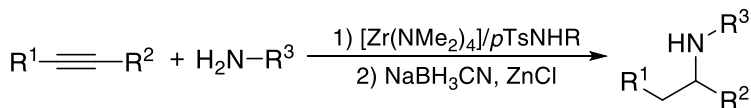
1. Catalyst for asymmetric intramolecular alkene hydroamination.
2. Catalyst used for secondary amine-tertiary amide transamidations.
3. Catalyst for the intermolecular hydroamination of alkynes with primary amines.
4. Catalyst for the hydroaminoalkylation of alkynes to generate the allylic amines.



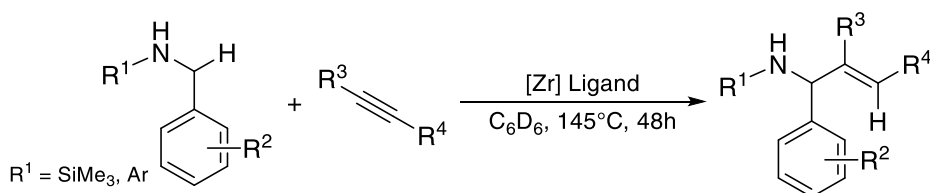
Tech Note (1)
Ref. (1)



Tech Note (2)
Ref. (2)



Tech Note (3)
Ref. (3)



Tech Note (4)
Ref. (4)

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CVD/ALD Applications

Thermal Behavior:

- Melting Point: 60°C [1,2], 58°C [3]
- Boiling Point: 80°C/0.05 Torr [1]
- Vapor pressure: 0.1 Torr/49°C, 1 Torr/77°C [2]
- Decomposition: >250°C [10]

Technical Notes:

1. ALD/CVD precursor for zirconium thin film deposition.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
ZrO ₂	ALD PEALD	75°C	1 Torr	H ₂ O	50-500°C 170-180°C	2 3
ZrN _x	ALD	75°C	0.20-0.35 Torr	NH ₃	150-250°C	4
Hf _{0.5} Zr _{0.5} O ₂	ALD	-	-	Hf(NMe ₂) ₄ , H ₂ O PL ₂ O ₂ -H ₂	175°C	5 6
(ZnTiZr) _x O _y	ALD	85°C	0.5 Torr	Ti(NMe ₂) ₄ , ZnEt ₂ , H ₂ O	200°C	7
Zr _x Al _{1-x} O _y	ALD	60°C	0.04 Torr	AlMe ₃ , H ₂ O	250°C	8
SrZrO ₃	ALD	60°C	1 Torr	Sr(Pr ₃ Cp) ₂ , H ₂ O	225°C	9
ZrO ₂ /Y ₂ O ₃	ALD	100°C	0.2-0.3 Torr	Y(MeCp) ₃ , H ₂ O	250°C	10
BaY _x Zr _y O _z	ALD	75°C	0.1 Torr	Ba(PrMe ₄ Cp) ₂ Y(MeCp) ₃ , H ₂ O	250-270°C	11
Li ₇ La ₃ Zr ₂ O ₁₂	ALD	80°C	-	AlMe ₃ , La-FMD, LiOBu, O ₃	225°C	12

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